

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants	Ishiduka, et al.	Examiner:	Johnson, Connie P.
Application No.:	10/591,718	Group Art Unit:	1722
Confirmation No:	3280	Docket:	1608-7 PCT/US/RCE II
Filed:	September 5, 2006	Dated:	July 26, 2011
For:	POSITIVE-TYPE RESIST COMPOSITION FOR LIQUID IMMERSION LITHOGRAPHY AND METHOD FOR FORMING RESIST PATTERN		

Commissioner for Patents
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Dated: July 26, 2011

Signature: Marcy Mancuso /Marcy Mancuso/

AMENDMENT AND RESPONSE PURSUANT TO 37 C.F.R. §1.111

Sir:

This is in response to the Office Action dated April 26, 2011, the due date for which is July 26, 2011. Entry of the amendments and reconsideration are respectfully requested.

Amendments to the Claims begin on page 2 of this submission.

Remarks begin on page 9 of this submission.